

Notice of References Cited	Application/Control No. 10/783,495		Applicant(s)/Patent Under Reexamination CHEN ET AL.	
	Examiner JENNIFER L. NORTON		Art Unit 2121	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2004/0203321	10-2004	Tsuchiyama et al.	451/006
*	B	US-6,304,999	10-2001	Toprac et al.	716/4
*	C	US-6,472,324	10-2002	Kusakabe et al.	438/692
*	D	US-7,012,670	03-2006	Park, Chan-Hoon	355/27
*	E	US-7,158,851	01-2007	Funk, Merritt	700/121
*	F	US-7,265,382	09-2007	Lymberopoulos et al.	257/48
*	G	US-6,825,912	11-2004	Park, Chan-Hoon	355/27
*	H	US-6,630,362	10-2003	Lensing, Kevin R.	438/14
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)			
	U	"A Run-to-Run Film Thickness Control of Chemical-Mechanical Planarization Process"; Jingang Yi, Wie-Shu Sang, Eugene Zhao; American Control Conference, Proceedings of the 2005 American Control Conference, (2005), pages 4231-4236			
	V				
	W				
	X				

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.